



1752  
TFU

**PATENT APPLICATION**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of

Docket No: Q62193

Kenichiro SATO, et al.

Appln. No.: 09/729,953

Group Art Unit: 1752

Confirmation No.: 7258

Examiner: John S Y CHU

Filed: December 06, 2000

For: POSITIVE TYPE PHOTORESIST COMPOSITION

**SUPPLEMENTAL REMARKS**

**MAIL STOP AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

At page 5 in the Remarks section of the Amendment filed December 20, 2005, Applicants referred to "resin (D) of the working examples of the present application." To clarify the record, Applicants note that they meant to refer to Resin D2 described at page 149 of the present specification. The undersigned notes that he left a voicemail message for the Examiner on today's date providing this clarification.

Respectfully submitted,

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WASHINGTON OFFICE

**23373**

CUSTOMER NUMBER

Date: January 31, 2006